Special Issue

Advances in Plasmonic Sensing Devices

Message from the Guest Editors

This Special Issue highlights the latest progress and innovations in the field of plasmonic sensors, optical sensors which exploit surface plasmon resonances to achieve high sensitivity and specificity in detecting various analytes. This issue covers a comprehensive range of plasmonic sensors, including Surface Plasmon Resonance sensors, Localized Surface Plasmon Resonance sensors, Surface-Enhanced Raman Scattering sensors, and other advanced technologies such as Plasmonic Colorimetric, Nanofiber, Photothermal, Metamaterial, Waveguide, and Fluorescence sensors. The scope includes the design and development of sensing systems, optimization of optical component arrangements, and the creation of novel plasmonic and optical materials. Applications span across biomedical, industrial, telecommunications, manufacturing, and environmental sectors, among many others. We welcome a wide range of paper types, including original research papers, reviews, and case studies, which contribute to the significant advancements in optical sensor technology, material development, system integration, and practical applications.

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